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## WHAT IS CLAIMED IS:

L	1.	A	method	for	fabricating	an	integrated	circuit
2	comprisin	g t	he steps	of:				

fabricating a portion of an integrated circuit comprising at least one active circuit area; and

fabricating a redistribution metal layer in said integrated circuit during a fabrication process of said portion of said integrated circuit.

2. The method as set forth in Claim 1 further comprising the step of:

fabricating portions of said redistribution metal layer that are open to receive a solder bump.

- 1 3. The method as set forth in Claim 1 further comprising the steps of:
- fabricating an active circuit area and an associated metal pad on a base substrate;
- fabricating a vertical plug of a redistribution metal layer;
- 7 mounting said vertical plug of said redistribution 8 metal layer on said metal pad;

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9	electrically	connecting	said	vertical	plug	of	said
10	redistribution met	al laver to	said r	metal pad;			

11 depositing an undoped silicon oxide layer on said
12 active circuit area and on said metal pad;

depositing a phosphosilicate glass layer on said undoped silicon oxide layer;

depositing a silicon oxynitride layer over said phosphosilicate glass layer;

depositing a flat redistribution metal layer over said silicon oxynitride layer; and

electrically connecting said flat redistribution metal layer to said vertical plug of said redistribution metal layer.

1 4. The method as set forth in Claim 3 further comprising the steps of:

depositing a polyimide layer over portions of said flat redistribution metal layer and over portions of said silicon oxynitride layer; and

etching portions of said polyimide layer to leave portions of said flat redistribution metal layer open to receive a solder bump.

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1	5.	The	method	as	set	forth	in	Claim	1	further
2	comprisir	na the	stens o	f.						

fabricating an active circuit area and an associated metal pad on a base substrate;

depositing an undoped silicon oxide layer on said active circuit area and on said metal pad;

depositing a phosphosilicate glass layer on said undoped silicon oxide layer;

depositing a redistribution metal layer over said phosphosilicate glass layer;

electrically connecting said redistribution metal layer to said metal pad; and

depositing a silicon oxynitride layer over portions of said redistribution metal layer.

- 6. The method as set forth in Claim 5 further comprising the step of:
- leaving portions of said redistribution metal layer
  open to receive a solder bump.

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1	7.	The	method	as	set	forth	in	Claim	5	further
2	comprisin	g the	step of	:						

depositing a silicon oxynitride layer over all portions of said redistribution metal layer.

8. The method as set forth in Claim 7 further comprising the step of:

etching said silicon oxynitride layer to a pattern that leaves portions of said redistribution metal layer uncovered to receive a solder bump.

9. The method as set forth in Claim 5 further comprising the steps of:

depositing a polyimide layer over portions of said redistribution metal layer and over portions of said silicon oxynitride layer; and

etching portions of said polyimide layer to leave portions of said flat redistribution metal layer open to receive a solder bump.

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1	10.	The	method	as	set	forth	in	Claim	1	further
2	comprisin	a the	step of	:						

fabricating said redistribution metal layer using a last metal layer that is used to fabricate an active circuit area of said integrated circuit.

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11.	An	integrated	circuit	comprising

- a portion of an integrated circuit comprising at least 2 one active circuit area; and 3
- a redistribution metal layer in said integrated circuit fabricated during a fabrication process of said portion of said integrated circuit. 6
  - 12. The integrated circuit as set forth in Claim 11 wherein portions of said redistribution metal layer in said integrated circuit are open to receive a solder bump.
  - The integrated circuit as set forth in Claim 11 further comprising:

an active circuit area and an associated metal pad on a base substrate;

- a vertical plug of a redistribution metal mounted on and electrically connected to said metal pad;
- a layer of undoped silicon oxide layer deposited on said active circuit area and on said metal pad;
- 9 a phosphosilicate glass layer deposited on undoped silicon oxide layer; 10



11	a	silicon	oxynitride	layer	deposited	on	said
12	phosphos	ilicate gl	lass laver: a	nd			

- a flat redistribution metal layer deposited over said silicon oxynitride layer;
- wherein said flat redistribution metal layer is electrically connected to said vertical plug of said redistribution metal layer.
  - 14. The integrated circuit as set forth in Claim 13 further comprising:
  - a polyimide layer deposited over portions of said flat redistribution metal layer and over portions of said silicon oxynitride layer;

wherein said polyimide layer is etched to leave portions of said flat redistribution metal layer open to receive a solder bump.

- 1 15. The integrated circuit as set forth in Claim 11 further comprising:
- an active circuit area and an associated metal pad on a base substrate;
- an undoped silicon oxide layer deposited on said active circuit area and on said metal pad;

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7	a	phosphosilicate	glass	layer	deposited	on	said
8	undoped	silicon oxide la	yer;				

- a redistribution metal layer deposited over said phosphosilicate glass layer, wherein said redistribution metal layer is electrically connected to said metal pad; and
- a silicon oxynitride layer deposited over portions of said redistribution metal layer.
- 16. The integrated circuit as set forth in Claim 15 wherein portions of said redistribution metal layer are open to receive a solder bump.
- 17. The integrated circuit as set forth in Claim 15 further comprising:
- a silicon oxynitride layer deposited over said redistribution metal layer etched to a pattern that leaves portions of said redistribution metal layer uncovered to receive a solder bump.

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1	18.	The	integrated	circuit	as	set	forth	in	Claim	15
2	further c	ompri	.sing:							

a polyimide layer deposited over portions of said redistribution metal layer and over portions of said silicon oxynitride layer;

wherein portions of said redistribution metal layer are open to receive a solder bump.

- 19. The integrated circuit as set forth in Claim 11 further comprising:
- a redistribution metal layer fabricated using a last metal layer that is used to fabricate an active circuit area of said integrated circuit.
- 1 20. The integrated circuit as set forth in Claim 12
  2 further comprising:
  - a solder bump attached to said portions of said redistribution metal layer of said integrated circuit that are open to receive a solder bump.

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1	21.	The	integrated	circuit	as	set	forth	in	Claim	14
2	further	compri	sing:							

a solder bump attached to said portions of said flat redistribution metal layer of said integrated circuit that are open to receive a solder bump.

22. The integrated circuit as set forth in Claim 16 further comprising:

a solder bump attached to said portions of said flat redistribution metal layer of said integrated circuit that are open to receive a solder bump.

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- 23. A method for fabricating an integrated circuit
  comprising the steps of:
  - fabricating a first portion of an active circuit area and an associated metal pad on a base substrate, said first portion of said active circuit area comprising a next to last metal layer;
    - depositing a passivation layer on said first portion of said active circuit area and on said metal pad;
    - etching at least one via through said passivation layer to said metal pad;
    - etching a metal layer pattern into said passivation layer;
    - depositing a last metal layer onto said metal layer pattern on said passivation layer to form a redistribution metal layer; and
- depositing said last metal layer onto said first
  portion of said active circuit area to form a complete
  active circuit area.

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1	24.	The	method	as	claimed	in	Claim	23	further
2	comprising	g the	step of:						

polishing a surface of said redistribution metal layer to produce a flat surface on said redistribution metal layer.

25. The method as claimed in Claim 23 further comprising the step of:

depositing said last metal layer into at least one via to electrically connect said metal pad to said redistribution metal layer.

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- 26. An integrated circuit comprising:
- 2 a first portion of an active circuit area and an
- 3 associated metal pad on a base substrate, said first
- 4 portion of said active circuit area comprising a next to
- 5 last metal layer;
  - a passivation layer deposited on said first portion of said active circuit area and on said metal pad;
    - at least one via etched through said passivation layer to said metal pad;
    - a metal layer pattern etched into said passivation layer; and
    - a redistribution metal layer deposited on said metal layer pattern in said passivation layer, wherein said redistribution metal layer comprises a last metal layer, and wherein a portion of said last metal layer is deposited on said first portion of said active circuit area to form a complete active circuit area.
    - 27. The integrated circuit as claimed in Claim 26 comprising metal within said at least one via, wherein said metal within said at least one via forms a unitary structure with said redistribution metal layer.

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- 28. The integrated circuit as claimed in Claim 27 wherein said metal within said at least one via electrically connects said metal pad to said redistribution metal layer.
- 29. The integrated circuit as claimed in Claim 26 wherein a surface of said redistribution metal layer deposited on said metal layer pattern in said passivation layer comprises a flat surface open to receive a solder bump.
- 30. The integrated circuit as claimed in Claim 29 further comprising:

a solder bump attached to said flat surface of said redistribution metal layer open to receive a solder bump.